

# A peak in density dependence of electron spin relaxation time in $n$ -type bulk GaAs in metallic regime

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We demonstrate that the peak in the density dependence of electron spin relaxation time in  $n$ -type bulk GaAs in the metallic regime predicted by Jiang and Wu [Phys. Rev. B **79**, 125206 (2009)] has been realized experimentally in the latest work by Krauß *et al.* [arXiv:0902.0270].

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Carrier spin lifetime in semiconductors has attracted much attention because of its essential role for the application of spintronic devices.<sup>1</sup> As reported, the electron spin lifetime can be strikingly long, even exceed 300 ns,<sup>2</sup> in  $n$ -type bulk GaAs at liquid helium temperature.<sup>3,4,5,6</sup> Due to the localized effect at such a low temperature, a very unusual behavior arises from the donor concentration dependence of the spin lifetime, where two maxima appear.<sup>4</sup> The one at relatively low doping concentration comes from the interplay of the hyperfine interaction and the anisotropic exchange interaction of donor-bound electrons, while the other one originates from the metal-to-insulator transition (MIT).<sup>7</sup> In the metallic regime, the D'yakonov-Perel'(DP) mechanism associated with the spin precession under the momentum-dependent effective magnetic field<sup>8</sup> together with spin-conserving scattering is recognized as the dominant electron spin relaxation mechanism in  $n$ -type semiconductors.<sup>4,9,10,11,12</sup> Very recently, Jiang and Wu studied the electron spin dynamics in bulk GaAs in *metallic* regime from a fully microscopic kinetic spin Bloch equation (KSBE) approach<sup>12,13,14</sup> and predicted a non-monotonic donor concentration dependence of the spin relaxation time, where the maximum spin relaxation time occurs at the crossover of the degenerate regime to the non-degenerate one, i.e., the corresponding Fermi temperature  $T_F$  at the peak comparable to the temperature of the electron plasma.<sup>9</sup> In a recent experiment, a peak in doping density dependence of electron spin relaxation time was also reported in optically excited  $n$ -type bulk GaAs at 4 K,<sup>15</sup> where the spin relaxation times are only several hundred picoseconds, shorter than the typical spin lifetime of the localized electron by two orders of magnitude.<sup>2</sup> This reveals that the peak should be associated with the spin dynamics in the *metallic* regime instead of the localized effect.<sup>15</sup> In that paper, by simply solving the KSBEs, the maximum spin relaxation time was interpreted as the interplay of the elastic impurity-carrier scattering, the inelastic carrier-carrier/phonon scattering, and the influence of screening.

In the present letter, we show that the physics of the peak is nothing but the one predicted by Jiang and Wu in Ref. 9. One would notice that the corresponding Fermi temperature at the experimental peak is around 90 K,

which is much higher than the lattice temperature. Even though the experiment was performed at 4 K, we will show that due to the laser-induced hot-electron effect, the electron temperature can be higher than the lattice temperature, and the underlying physics of the peak is coincident with that proposed by Jiang and Wu, i.e., the crossover of the degenerate regime to the non-degenerate one.

We study electron spin dynamics in  $n$ -type bulk GaAs in metallic regime from the fully microscopic KSBEs derived via the nonequilibrium Green function method,<sup>12,13,16,17</sup>

$$\partial_t \rho_{\mathbf{k}} = \partial_t \rho_{\mathbf{k}}|_{\text{coh}} + \partial_t \rho_{\mathbf{k}}|_{\text{scat}}, \quad (1)$$

where  $\rho_{\mathbf{k}}$  is the density matrix of the electron with momentum  $\mathbf{k}$ .  $\partial_t \rho_{\mathbf{k}}|_{\text{coh}}$  is the coherent term, which describes the spin precession under the effective magnetic field originating from the Dresselhaus spin-orbit coupling (SOC)<sup>18</sup> and Coulomb Hartree-Fock (HF) terms.<sup>9,12</sup>  $\partial_t \rho_{\mathbf{k}}|_{\text{scat}}$  represents the scattering term, including all the relevant scatterings, such as the electron-impurity, electron-phonon, electron-electron, and electron-hole scatterings. Both lattice-temperature longitudinal optical (LO) phonon and acoustic (ac) phonon are included in our KSBEs. The details of Eq. (1) can be found in Ref. 9.

For optically excited setup in  $n$ -type GaAs, the total electron density  $N_e = N_{ex} + N_D$ , with  $N_{ex}$  and  $N_D$  representing those from photo-excited process and  $n$ -type dopant, respectively.  $N_D$  equals to the impurity density  $N_i$  for Si-doped GaAs.<sup>5</sup> Initially,  $N_D$  is in the thermal equilibrium state at lattice temperature  $T_L$ , and the photo-excited carriers are in Gaussian distribution with the center energy  $\hbar\nu = 1.55$  eV in this work. The optimal polarization of  $N_{ex}$  generated by a circularly polarized pump pulse is 50 %, according to the optical selection rule. Experimental and theoretical studies on ultrafast hole spin dynamics reveal that holes lose their polarization information within sub-picosecond in bulk GaAs.<sup>19,20</sup> Therefore, it is reasonable to employ a time-independent thermal equilibrium hole distribution with the density  $N_h = N_{ex}$  in the time scale of interest here (several hundred picoseconds). We take the hole temperature equals to the hot-electron temperature approx-

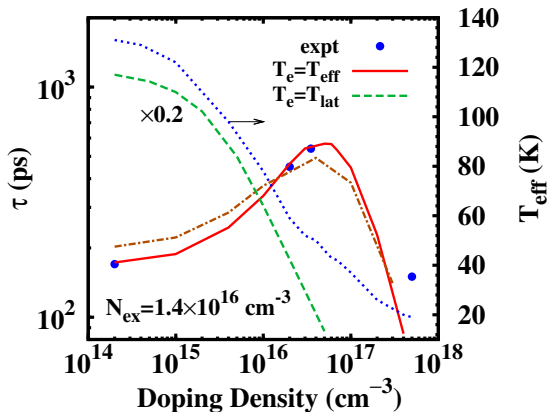


FIG. 1: (Color online) Electron spin relaxation times from the calculation via the KSBE approach (red solid curve) and from the experiment<sup>15</sup> (blue  $\bullet$ ) as function of the doping density. The green dashed curve shows the results without hot-electron effect. In the calculation, the Dresselhaus SOC  $\gamma_D = 26 \text{ eV}\cdot\text{\AA}^3$ ,<sup>21</sup> photo-excited carrier density  $N_{ex} = 1.4 \times 10^{16} \text{ cm}^{-3}$ , and the photon energy  $\hbar\nu = 1.55 \text{ eV}$ . The hot-electron temperature used in the computation is plotted as the blue dotted curve (Note the scale is on the right hand side of the frame). The chain curve is the calculated spin relaxation time with a fixed hot-electron temperature 80 K, and  $N_{ex} = 6 \times 10^{15} \text{ cm}^{-3}$ .

imately. The time evolution of the electron polarization signals  $\langle s_z \rangle = \sum_{\mathbf{k}} \text{Tr}(\rho_{\mathbf{k}} s_z)$  is obtained by numerically solving KSBEs.

In Fig. 1, the electron spin relaxation time is plotted as a function of the doping density with the photo-excited electron density  $N_{ex} = 1.4 \times 10^{16} \text{ cm}^{-3}$  as the red solid curve. It is seen that the spin relaxation time presents a non-monotonic doping-density dependence with the maximum achieved at around  $N_D = 5 \times 10^{16} \text{ cm}^{-3}$ , which is in good agreement with the experimental data (blue  $\bullet$ ).<sup>15</sup> This feature can be explained by  $\tau \sim 1/[\langle |\mathbf{\Omega}(\mathbf{k})|^2 - \Omega_z^2(\mathbf{k}) \rangle \tau_p^*]$  in the strong scattering limit,<sup>1,9,12,22,23,24</sup> in which  $\mathbf{\Omega}$  represents the inhomogeneous effective magnetic field and  $\tau_p^*$  stands for the averaged effective momentum scattering time. From our calculation, we find that the momentum relaxation process of photo-excited carriers is completed within a few picoseconds, leaving the electron distribution as a Fermi distribution with the hot-electron temperature different from the lattice one. We plot the hot-electron temperature  $T_{eff}$  as a function of the doping density as the blue dotted curve. This hot-electron temperature is exactly the one used in the computation of spin relaxation time. We find that the hot-electron temperature is beyond 100 K at low doping density, much higher than the lattice temperature  $T_{lat}$ , and decreases significantly with the increase of doping density. Therefore, the system is non-degenerate (degenerate) in the low (high) doping regime. According to Ref. 9, in the non-degenerate regime, i.e.,  $T_e \gg T_F$ , the inhomogeneous broadening  $\langle |\mathbf{\Omega}(\mathbf{k})|^2 - \Omega_z^2(\mathbf{k}) \rangle$  is insensitive to the

doping density, and the electron-electron scattering time  $\tau_p^{ee}$ , electron-hole scattering time  $\tau_p^{eh}$ , and the electron-impurity scattering time  $\tau_p^{ei}$  all decrease with increasing doping density. As a result, the spin relaxation time  $\tau$  increases with the doping density according to the motional narrowing relation. Contrarily, the increase of the inhomogeneous broadening becomes more efficient than the change of  $\tau_p^*$ , and hence reduces  $\tau$  in the degenerate regime.<sup>9</sup> The crossover between the degenerate and non-degenerate regimes can be estimated by the Fermi temperature  $T_F$ .<sup>9</sup> At the peak ( $N_D \sim 5 \times 10^{16} \text{ cm}^{-3}$ ),  $T_F$  ( $\sim 90 \text{ K}$ ) is comparable to the hot-electron temperature ( $\sim 45 \text{ K}$ ), which is coincident with the theory of Ref. 9. For comparison, we also plot the results without the hot-electron effect, i.e.,  $T_e = T_{lat}$ , as the green dashed curve. It is seen that the spin relaxation time is much longer than the result with the hot-electron effect at low doping density and decreases monotonically with increasing the doping density. The underlying physics of the short spin relaxation time due to the hot-electron effect in the low doping regime is that the high hot-electron temperature drives the electrons to the states with a larger momentum and hence enhances the inhomogeneous broadening. Therefore the spin relaxation time decreases drastically. The monotonic decrease of the spin relaxation time is because that the electron-hole plasma is strongly degenerate in the entire range of doping density due to the low temperature.

One notices that the hot-electron temperature at the peak is about one half of  $T_F$ , instead of  $T_e \approx T_F$  as predicted in Ref. 9. This results from the varied hot-electron temperature at different doping densities. In the low doping regime, the high hot-electron temperature reduces the spin relaxation time, which leads the peak to the relatively high doping regime. The brown chain curve shows the calculation with a fixed hot-electron temperature at 80 K, where the relation  $T_e \approx T_F$  at the peak is satisfied.<sup>9</sup>

To examine the role of the external magnetic field, we turn on the magnetic field in the coherent term in Eq. (1). We choose  $B = 4 \text{ T}$  in the Voigt configuration following the experimental scheme.<sup>15</sup> We find that the electron spin relaxation time determined by the DP mechanism is only marginally different (not shown) from the zero-field results, which agrees with the previous experiment.<sup>5</sup>

In summary, we have investigated the electron spin dynamics from the fully microscopic KSBEs in *n*-type bulk GaAs. We demonstrate that the peak observed in the latest experiment<sup>15</sup> gives the strong evidence of the prediction by Jiang and Wu<sup>9</sup> via analyzing the laser induced hot-electron effect.

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